	Туре	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	0	etching and chamber and oxide adj3 gas and metal with layer and (( "CL.sub2."CL2 cloride) with (triflouromethan e CHF3	; EPO;	2005/12/1 5 14:22
2	BRS	L2	0	cleaning with etching and chamber and oxide adj3 gas and metal with		2005/12/1 5 14:19
3	BRS	L3		etching and chamber and oxide adj3 gas and metal and layer and (( "CL.sub2."CL2 cloride) with (triflouromethan e CHF3	; EPO;	2005/12/1 5 14:20
4	BRS	L4	0	etch\$3 and chamber and oxide and gas and metal and layer and (( "CL.sub2."CL2 cloride) and (triflouromethan e CHF3	; EPO;	2005/12/1 5 14:21

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	Туре	L #	Hits	Search Text	DBs	Time Stamp
5	BRS	L5	0	clean\$3 and etch\$3 and oxide and gas and metal and layer and (( "CL.sub2."CL2 cloride) and (triflouromethan e CHF3	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWE	2005/12/1 5 14:22
6	BRS	L6	0	layer and (( "CL.sub2."CL2 cloride) and (triflouromethan e CHF3 "chf.sub3."))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWE	2005/12/1 5 14:23
7	BRS	L7	2154 38	oxide and gas and metal and layer	US- PGPUB; USPAT; USOCR; EPO; DERWE NT	2005/12/1 5 14:22
8	BRS	L8	156	cleaning with etching and chamber and oxide adj3 gas and metal with layer	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWE	2005/12/1 5 14:22

	Туре	L #	Hits	Search Text	DBs	Time Stamp
9	BRS	L9	けんし	clean\$3 with etch\$3 and chamber and oxide adj3 gas and metal with layer	US- PGPUB; USPAT; USOCR; EPO; DERWE NT	2005/12/1 5 14:30
10	BRS	L1 0	0	(( "CL.sub2."CL2 cloride) and (triflouromethan e CHF3 "chf.sub3."))	; USOCR ; EPO; JPO; DERWE NT	2005/12/1 5 14:23
11	BRS	L1 1	169	CL2 cloride) and (triflouromethan e CHF3	1.	2005/12/1 5 14:24
12	BRS	L1 2	2	9 and 11	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWE	2005/12/1 5 14:24

	Туре	L #	Hits	Search Text	DBs	Time Stamp
13	BRS	L1 3	1			2005/12/1 5 14:30